

UNITED STATES PATENT AND TRADEMARK OFFICE
CERTIFICATE OF CORRECTION

PATENT NO. : 5,397,432
DATED : March 10, 1995
INVENTOR(S) : Konno, et. Al.

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Column 11, line 39, delete "or" insert therefor --and --.

note
should be deleted; and substitute therefor, the

Column 10-11, Table 1, ~~insert symbols~~

attached Table 1.

See attached sheet

Table 1

Conditions	Amount of residual chlorine $\mu\text{m g/cm}^2$ 10^{15}atoms/cm^2		After- corrosion	Symbols shown in Fig. 9
① Etching only	0.92 ± 0.06	16.0 ± 1.0	Large	○
② Downflow ashing using O_2 after ①	0.89 ± 0.06	15.5 ± 1.0	Large	●
③ Downflow ashing using $\text{O}_2 + \text{CF}_4$ after ①	0.54 ± 0.03	9.3 ± 0.4	Small	■
④ Downflow ashing using $\text{O}_2 + \text{H}_2\text{O}$ after ①	0.23 ± 0.03	4.0 ± 0.5	No	◇
⑤ Exposure to H_2O after ② (30sec)	0.51 ± 0.02	8.7 ± 0.3	Small	▲
⑥ Exposure to H_2O after ② (90sec)	0.48 ± 0.01	8.1 ± 0.2	Small	▲
⑦ Exposure to H_2O after ② (180sec)	0.45 ± 0.04	7.6 ± 0.7	Small	▲
⑧ Downflow treatment using H_2O after ② (30sec)	0.28 ± 0.01	4.7 ± 0.2	None	△
⑨ Downflow treatment using H_2O after ② (90sec)	0.15 ± 0.00	2.5 ± 0.0	No	△
⑩ Downflow treatment using H_2O after ② (180sec)	0.11 ± 0.01	1.9 ± 0.1	No	△
⑪ Downflow treatment using H_2 after ② (30sec)	0.68 ± 0.01	11.8 ± 0.2	Small	▼
⑫ Downflow treatment using H_2O after ② (90sec)	0.68 ± 0.01	11.7 ± 0.1	Small	▼
⑬ Downflow treatment using H_2 after ② (180sec)	0.64 ± 0.01	11.1 ± 0.2	Small	▼

Exposure to H_2O : heated at 120°C in water vapor at 0.1 Torr.